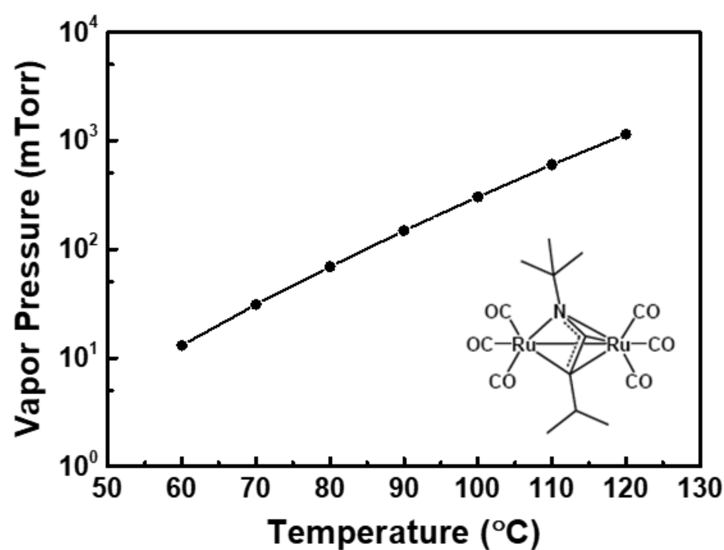

Figure 1. Vapor pressure and molecule structural information of novel Ru precursor (T-Rudic)

Reference

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